

# **Come join us for lunch and learn more about ZEISS Mask CDU Control Solutions!**

During the BACUS Conference 2010 you will continue to hear about mask designs of ever heightening design complexity that result in tighter specifications for Mask Critical Dimension Uniformity (CDU).

May we invite you for lunch to provide a brief overview of the industry-proven method to optimize your mask CD Uniformity with the CDC200 even after the mask has been written. As introduction an overview of the ZEISS aerial imaging system WLCD32 will explain the input for the CDC200 and the verification of the CD uniformity improvement. Both systems built up a closed-loop solution enabling highest mask performance.

**Please join us for a "Lunch & Learn Session"!**

Date: Wednesday, September 15<sup>th</sup>, 2010

Time: 12:00 – 1:00pm

Place: Santa Barbara Room, Marriott Hotel

Please register for the event at: Jim Polcyn, [polcyn@smt.zeiss.com](mailto:polcyn@smt.zeiss.com)

